

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Kazuya KAMON

Application No.: 09/320,946

Filed: May 26, 1999

For: PHOTOMASK, FABRICATION
METHOD OF PHOTOMASK, AND
FABRICATION METHOD OF
SEMICONDUCTOR INTEGRATED
CIRCUIT



Group Art Unit: 1756

Examiner: S. Mohamedulla

#14613
10/24/01

PETITION FOR EXTENSION OF TIME

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

The following extension of time is requested to respond to Office Action dated June 19, 2001:
one month to October 19, 2001; the extension fee is:

☐ \$55.00 (215) ☒ \$110.00 (115).

☐ The shortened statutory period has been reset by an Advisory Action dated _____.

☒ An extension fee in the amount of \$ 110.00 is enclosed.

☐ Charge \$ _____ to Deposit Account No. 02-4800.

The Commissioner is hereby authorized to charge any appropriate fees under 37 C.F.R. §§ 1.16, 1.17 and 1.21 that may be required by this paper, and to credit any overpayment, to Deposit Account No. 02-4800. This paper is submitted in duplicate.

10/19/2001 NROCHA1 00000097 09320946

02 FC:115

110.00 OP

Respectfully submitted,

BURNS, DOANE, SWECKER & MATHIS, L.L.P.

By: _____

Ellen Marcie Emas
Registration No. 32,131

P.O. Box 1404
Alexandria, Virginia 22313-1404
(703) 836-6620
Date: October 18, 2001

RECEIVED
OCT 23 2001
TC 1700